



#7/Amdt A  
3-11-03  
gld

PATENT  
Customer No. 22,852  
Attorney Docket No. 08244.0032

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
)  
Sung-chan PARK et al. ) Group Art Unit: 2813  
)  
Application No.: 09/998,303 ) Examiner: T. Nguyen  
)  
Filed: December 3, 2001 )  
)  
For: METHOD FOR FORMING )  
CONTACT HOLD AND SPACER )  
OF SEMICONDUCTOR DEVICE )

RECEIVED  
DEC-5 2002  
TECHNOLOGY CENTER 2800

Commissioner for Patents  
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action dated July 31, 2002, the period for reply having been extended for one month to December 2, 2002 (November 30, 2002 being a Saturday) by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE CLAIMS:

Please cancel claims 10-20 without prejudice or disclaimer of the subject matter thereof, and amend claims 1, 6 and 8 as follows:

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SUB 317 1. (Amended) A method for forming contact openings between bit line patterns, the method comprising the steps of:

A/t  
CMT